

# CPW3-0650-S004B-Silicon Carbide Schottky Diode Chip

$Z$ - $Rec^{TM}$ Rectifier		V <sub>RRM</sub>	= 650 V
		I <sub>F(AVC</sub>	<sub>3)</sub> = 4 A
Features	Chip Outline	$\mathbf{Q}_{c}$	= 8.5 nC
650 Volt Schottly, Postifier			

- 650-Volt Schottky Rectifier ۰
- Zero Reverse Recovery •
- Zero Forward Recovery •
- •
- High-Frequency Operation Temperature-Independent Switching Behavior •
- Extremely Fast Swtitching •
- Positive Temperature Coefficient on  $V_{F}$ •



Part Number	Anode	Cathode	Package	Marking
CPW3-0650-S004B	AI	Ni/Ag	Sawn on Foil	Wafer # on Foil

## **Maximum Ratings**

Symbol	Parameter	Value	Unit	Test Conditions	Note
V <sub>RRM</sub>	Repetitive Peak Reverse Voltage	650	V		
V <sub>RSM</sub>	Surge Peak Reverse Voltage	650	V		
V <sub>DC</sub>	DC Blocking Voltage	650	V		
I <sub>F(AVG)</sub>	Average Forward Current	4	А	T <sub>1</sub> =160°C	
I <sub>FRM</sub>	Repetitive Peak Forward Surge Current	22	А	$T_c=25^{\circ}C$ , $t_p=10$ ms, Half Sine Wave, D=0.3	1
I <sub>FSM</sub>	Non-Repetitive Peak Forward Surge Current	110	А	$T_c=25^{\circ}C$ , $t_p=10 \ \mu s$ , Pulse	1
T <sub>J</sub> , T <sub>stg</sub>	Operating Junction and Storage Temperature	-55 to +175	°C		



#### **Electrical Characteristics**

Symbol	Parameter	Тур.	Max.	Unit	Test Conditions	Note
V <sub>F</sub>	Forward Voltage	1.5 1.8	1.8 2.4	V	$I_F = 4 A T_J = 25^{\circ}C$ $I_F = 4 A T_J = 175^{\circ}C$	
I <sub>R</sub>	Reverse Current	12 24	60 120	μA	$V_{R} = 650 V T_{J} = 25^{\circ}C$ $V_{R} = 650 V T_{J} = 175^{\circ}C$	
Q <sub>c</sub>	Total Capacitive Charge	8.5		nC	$V_{R} = 650 \text{ V}, I_{F} = 4 \text{ A}$ $di/dt = 500 \text{ A}/\mu\text{s}$ $T_{J} = 25^{\circ}\text{C}$	
с	Total Capacitance	251 22 21		pF	$V_{R} = 0 V, T_{J} = 25^{\circ}C, f = 1 MHz$ $V_{R} = 200 V, T_{J} = 25^{\circ}C, f = 1 MHz$ $V_{R} = 400 V, T_{J} = 25^{\circ}C, f = 1 MHz$	

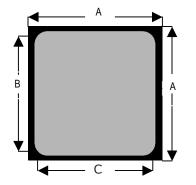
Note: 1. Assumes  $\theta {\sf JC}$  Thermal Resistance of 2.02°C/W or less

#### **Mechanical Parameters**

Parameter	Тур.	Unit
Die Size	1.13 x 1.13	mm
Anode Pad Size	0.98 x 0.99	mm
Anode Pad Opening	0.87 x 0.88	mm
Thickness	377 ± 10%	μm
Wafer Size	100	mm
Anode Metalization (Al)	4	μm
Cathode Metalization (Ni/Ag)	1.8	μm
Frontside Passivation	Polyimide	



### **Chip Dimensions**



symbol	dimension			
	mm inch			
A	1.13	0.044		
В	0.98	0.039		
C	0.99	0.039		

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The die-on-tape method of delivering these SiC die may be considered a means of temporary storage only. Due to an increase in adhesion over time, die stored for an extended period may affix too strongly to the tape. These die should be stored in a temperature-controlled nitrogen dry box soon after receipt. Cree will further recommend that all die be removed from tape to a waffle pack, to a similar storage medium, or used in production within 2 – 3 weeks of delivery to assure 100% release of all die without issues.

This product has not been designed or tested for use in, and is not intended for use in, applications implanted into the human body nor in applications in which failure of the product could lead to death, personal injury or property damage, including but not limited to equipment used in the operation of nuclear facilities, life-support machines, cardiac defibrillators or similar emergency medical equipment, aircraft navigation or communication or control systems, air traffic control systems, or weapons systems.

Cree, Inc. 4600 Silicon Drive Durham, NC 27703 USA Tel: +1.919.313.5300 Fax: +1.919.313.5451 www.cree.com/power

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